Notice of Allowability	Application No.	No. Applicant(s)	
	10/621,696	LIOU, HUEY-CHIANG	
	Examiner	Art Unit	(Ann)
	Nitin Parekh	2811	(1/00
The MAILING DATE of this communication apper All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT Ri- of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED or other appropriate comn GHTS. This application is	in this application. If not includ nunication will be mailed in due	ed course. THIS
1. This communication is responsive to <u>12-13-04</u> .			
2. The allowed claim(s) is/are <u>2,4-11,13-20,22-25 and 28-31</u> .			
3. The drawings filed on 16 July 2003 are accepted by the Ex	aminer.		
4. Acknowledgment is made of a claim for foreign priority un	der 35 U.S.C. § 119(a)-(d)	or (f).	
a) All b) Some* c) None of the:			
1. Certified copies of the priority documents have		iam Nia	
2. Certified copies of the priority documents have	• •	·	tion from the
 Copies of the certified copies of the priority doc International Bureau (PCT Rule 17.2(a)). 	aments have been receive	eu iii ulis nauona: stage applica	
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE"	of this communication to fi	le a reply complying with the re	quirements
noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		ie a reply complying with the re	quirements
5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give			IOTICE OF
6. CORRECTED DRAWINGS (as "replacement sheets") mus	t be submitted.		
(a) ☐ including changes required by the Notice of Draftspers	on's Patent Drawing Revie	ew (PTO-948) attached	
1) ☐ hereto or 2) ☐ to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date	Amendment / Comment o	or in the Office action of	
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the			e back) of
7. DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT I			Note the
Attachment(s) 1. ☑ Notice of References Cited (PTO-892)	5 ☐ Notice of I	nformal Patent Application (PT	O-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)		Summary (PTO-413),	- ··,
	Paper No	./Mail Date	
3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date	<i>.</i> –	s Amendment/Comment	
4. Examiner's Comment Regarding Requirement for Deposit		s Statement of Reasons for Allo	owance
of Biological Material	9. 🗍 Other	 Nttin Parekh Primary Examiner Technology Center	r 2800

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DETAILED ACTION

Allowable Subject Matter

- 1. Claims 2, 4-11, 13-20, 22-25 and 28-31 are allowed.
- 2. Cancel claims 12, 26 and 27.
- 3. Claims 1, 3 and 21 have been canceled.

Examiner's Amendment

- 4. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.
 - A. Cancel claims 12, 26 and 27.
 - B. Claim 2, line 16: Delete "sacrificial" and Insert "the sacrificial" —.
 - C. Claim 2, line 22: Delete "sacrificial" and Insert --- "the second sacrificial" ---.
 - D. At the end of claim 2, line 23: Insert "and forming vertical support structures peripheral to the conductive vertical series, wherein removing portions of the sacrificial dielectric decomposition product further forms air gaps between the vertical support structures and the conductive vertical series." —.
 - E. Claim 13, line 1: Delete "claim 12" and Insert --- "claim 2" ---.

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F. At the end of claim 29, line 16: Insert — "positioning a first capping layer adjacent to the surfaces of the two additional conductive layers and applying a tensile load in a direction substantially parallel to a substrate layer to the first capping layer such that the first capping layer is adhered to the two additional conductive layers separated by the air gap" -

Authorization for this examiner's amendment was given in a telephone interview with Michael Bernadicou on 08-04-05.

Reasons for Allowance

5. The following is an examiner's statement of reasons for allowance:

The references of record do not teach either singularly or in combination at least the limitations "vertical support structures peripheral to the conductive vertical series and isolated from the conductive vertical series by air gaps wherein none of the peripheral vertical support structures are between the at least two conductive vertical series" and "a capping layer adjacent to and above upper surfaces of the vertical support structures" in an air gap interconnect structure having at least two conductive vertical series adjacent the substrate layer wherein each conductive vertical series having a plurality of conductive layers is isolated from each other by air gaps defined by side walls of the conductive vertical series; or "the interconnect comprising conductive layers positioned

in at least two conductive vertical series, the conductive vertical series isolated from each other by sacrificial dielectric material; forming a protective layer adjacent the interconnect; patterning the protective layer to expose portions of the sacrificial dielectric material; decomposing portions of the sacrificial dielectric material to form a sacrificial dielectric decomposition product; removing portions of the sacrificial dielectric decomposition product to form air gaps between the conductive layers" and "forming vertical support structures peripheral to the conductive vertical series, wherein removing portions of the sacrificial dielectric decomposition product further forms air gaps

between the vertical support structures and the conductive vertical series" in a method

of forming an air gap in a multi-layer interconnect.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Nitin Parekh whose telephone number is 571-272-1663. The examiner can normally be reached on 09:00AM-05:30PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's acting supervisor, Steven Loke can be reached on 571-272-1657. The fax phone

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number for the organization where this application or proceeding is assigned is 571-

273-8300.

Information regarding the status of an application may be obtained from the

Patent Application Information Retrieval (PAIR) system. Status information for published

applications may be obtained from either Private PAN or Public PAG. Status information

for unpublished applications is available through Private PAIR only. For more

information about the PAIR system, see http://pair-direct.uspto.gov. Should you have

questions on access to the Private PAG system, contact the Electronic Business Center

(EBC) at 866-217-9197 (toll-free). Any inquiry of a general nature or relating to the

status of this application or proceeding should be directed to the receptionist whose

telephone number is 703-308-0956.

Natur Pareth

NP

NITIN PAREKH

PRIMARY EXAMINER

08-04-05

TECHNOLOGY CENTER 2800